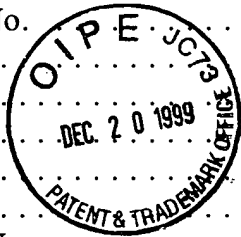


#6/Amdt B  
12/28/99  
C. McKinney

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/059,644  
Filing Date April 13, 1998  
Inventor Pai-Hung Pan  
Assignee Micron Technology, Inc.  
Group Art Unit 2822  
Examiner M. Trinh  
Attorney's Docket No. MI22-898  
Title: Semiconductor Processing Methods Of Forming A Conductive Gate and Line



RESPONSE TO SEPTEMBER 16, 199 OFFICE ACTION

To: Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
601 W. First Avenue, Suite 1300  
Spokane, WA 99201-3828

Sir:

Responsive to the Office Action dated September 16, 1999,  
Applicant amends and remarks as follows [unless otherwise indicated,  
deletions are bracketed, additions are underlined]:

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AMENDMENTS

In the Claims

In Claim 43, at line 2, insert --layer-- after the phrase "overlying  
metal".

In Claim 46, at line 1, replace "said" with --the--.

In Claim 51, at line 4, replace "anisotropically" with  
--anisotropically--.

B